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<b>Substitute for form 1449</b>  <b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (use as many sheets as necessary)				<b>Complete if Known</b>	
				<b>Application Number</b>	10/018,406
				<b>Filing Date</b>	December 13, 2001
				<b>First Named Inventor</b>	Charles E. Wickersham, Jr.
				<b>Art Unit</b>	1742
				<b>Examiner Name</b>	
<b>Sheet</b>	<b>1</b>	<b>of</b>	<b>4</b>	<b>Attorney Docket Number</b>	TSO 190 P2

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. <sup>1</sup>	Document Number Number - Kind Code <sup>2</sup> (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
MA		US-2,790,216	4-30-1957	Hunter	
MA		US-4,054,173	10-18-1977	Hickam	
MA		US-4,568,007	2-4-1986	Fishler	
MA		US-5,160,388	11-3-1992	Legresy et al.	
MA		US-5,369,063	11-29-1994	Gee et al.	
MA		US-5,406,850	4-18-1995	Bouchard et al.	
MA		US-5,559,614	9-24-1996	Urbish et al.	
MA		US-5,636,681	6-10-1997	Sulzer et al.	
MA		US-5,738,767	4-14-1998	Coad et al.	
MA		US-5,827,409	10-27-1998	Iwata et al.	

FOREIGN PATENT DOCUMENTS						
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MA		EP 0 211 401 B1	05-06-1992	General Electric Company		
MA		EP 0 418 846 B1	02-08-1995	Honeywell, Inc.		
MA		EP 0 665 193 A2	08-02-1995	Intevac, Inc.		
MA		EP 0 467 659 B1	03-06-1996	Sharp Kabushiki Kaisha		

<b>Examiner Signature</b>	<i>Melvyn Andrews</i>	<b>Date Considered</b>	11-20-03
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ma		US-5,887,481	3-30-1999	Leroy et al.	
ma		US-5,943,559	8-24-1999	Maeda	
ma		US-5,955,673	9-21-1999	Leroy et al.	
ma		US-5,989,782	11-23-1999	Nishiki et al.	
ma		US-6,001,227	12-14-1999	Pavate et al.	
		<del>US-6,017,779</del>	<del>1-25-2000</del>	<del>Miyasaka</del> <b>DUPLICATE</b>	
ma		US-6,019,657	2-1-2000	Chakvorty et al.	
ma		US-6,020,946	2-1-2000	Callegari et al.	
ma		US-6,057,557	5-2-2000	Ichikawa	
ma		US-6,139,701	10-31-2000	Pavate et al.	

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ma		EP 0 412 843 B1	05-29-1996	Sharp Kabushiki Kaisha		
ma		EP 0 561 161 B1	04-23-1997	Corning Incorporated		
ma		WO 99/64854	12-16-1999	Tosoh SMD, Inc.		
ma		WO 00/15863	3-23-2000	Tosoh SMD, Inc.		

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**OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS**

Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T <sup>2</sup>
		*BARNES, M.S. et al., <i>Phys. Rev. Letter</i> , (1992) 68, 313.	
		*GOREE J. et al., <i>J. Vac. Sci. Technol.</i> , (1992) A10, 3540.	
		*NADEL, S.J. et al., <i>35th Tech. Conf. Proc. Society of Vacuum Coaters</i> , (1992) 365.	
		*ANDERSON, L., <i>35th Tech. Conf. Proc. Society of Vacuum Coaters</i> , (1992) 325.	
		*SCHOLL, R.A., <i>37th Tech. Conf. Proc. Society of Vacuum Coaters</i> , (1994) 312.	
		*BAILEY, R.S. et al., <i>VMIC Conference, ISMIC</i> , (1994) 317.	
		*LEE, F. et al., <i>Microcontamination</i> , (1994) 12, 33.	
ma		DANOVICH, D. et al., "Sputtering Issues for Flat-Panel Displays," <i>Information Display</i> , (November 1995), pp. 26-27, 30-31.	
		*TAKAHASHI, K.M. et al., <i>J. Vac. Sci. Technol.</i> , (1996), A14, 2983.	
		*SELWYN, G.S. et al., <i>J. Vac. Sci. Technol.</i> , (1997) A15, 2023.	
		*EERNISSE, E.P. et al., <i>J. Appl. Phys.</i> , (1997) 48, 91	
		*MONTEIRO, O.R. et al., <i>IEEE Trans. Plasma Science</i> , (1999) 27, 1030.	
		*ABBURI, M. et al., <i>Solid State Technology</i> , (1999) 42, 55.	

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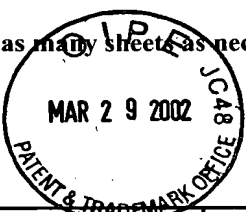
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		*SELWYN, G.S. et al., <i>Appl. Phys. Letter</i> , (1876) p. 57.	
		*VON GÜNTHERSCHULZE, A., <i>Z. Physik</i> , (1933) 86, 778.	
		*FREITAG, W.O. et al., <i>2nd Symposium on Deposition of Thin Films by Sputtering</i> , CVC, Rochester, NY, (June 1967) p. 92.	
		*ROBINSON, I.E. et al., <i>J. Nuclear Mat.</i> , (1976) 63, 432.	
		*WEHNER, G.K., <i>J. Vac. Sci. Technol.</i> , (1985) A3, 1821.	
		*ROTH, R.M. et al., <i>Appl. Phys. Letter</i> , (1985) 46, 253.	
		*SPEARS, K.G. et al., <i>IEEE Trans. Plasma Sci.</i> , (1986) PS 14, 179.	
		*SELWYN, G.S. et al., <i>J. Vac. Sci. Technol.</i> , (1989) A7, 2758.	
		*JELLUM, G.M. et al., <i>J. Appl. Phys.</i> , (1990) 67, 6490.	
		*ANDERSON, H.M. et al., <i>J. Applied Physics</i> , (1990) 67, 3999.	
		*SELWYN, G.S. et al., <i>J. Vac. Sci. Technol.</i> , (1990) A8, 1726.	
		*AKARI, K. et al., <i>Surf. Coatings &amp; Technol.</i> , (1990) 43-44, 312.	
		*SMADI, M.M. et al., <i>J. Vac. Sci. Technol.</i> , (1992) B10, 30.	
		*LOGAN, J.S. et al., <i>J. Vac. Sci. Technol.</i> , (1992) A10, 1875.	
		*YOO, W.J. et al., <i>Appl. Phys. Letter</i> , (1992) 60, 1073.	
ma		*FOSTER, H.I. et al., "A Modular Approach to Sputter Coating of Flat Panel Displays," <i>Society of Vacuum Coaters 35th Annual Technical Conference</i> (1992) pp. 357-361.	

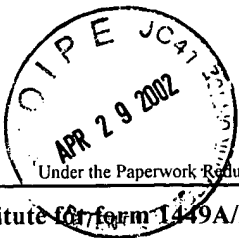
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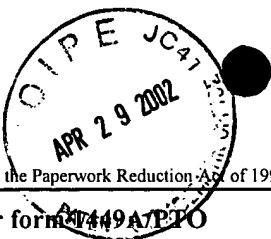
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ma		FREITAG, W.O. et al., "Diode Sputtering of Cermet Films," <i>2nd Symposium on Deposition of Thin Films by Sputtering</i> , University of Rochester and Consolidated Vacuum Corporation, Rochester, NY, June 1967, pp. 92-96.	
ma		ROBINSON, J.E. et al., "Models for Chunk Sputtering," <i>Journal of Nuclear Materials</i> , 1976, Vol. 63, pp. 432-437, North-Holland Publishing Company.	
ma		EERNISSE, E.P. et al., "Role of Integrated Lateral Stress in Surface Deformation of He-Implanted Surfaces," <i>Journal of Applied Physics</i> , January 1, 1977, Vol. 48, No. 1, pp. 9-17, American Institute of Physics.	
ma		ROTH, R.M. et al., "Spatial Dependence of Particle Light Scattering in an RF Silane Discharge," <i>Appl. Phys. Letter</i> , February 1, 1985, Vol. 46, No. 3, pp. 253-255, American Institute of Physics.	
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ma		SELWYN, G.S. et al., "In Situ Laser Diagnostic Studies of Plasma-Generated Particulate Contamination," <i>J. Vac. Sci. Technol.</i> , July/August 1989, A 7, (4) pp. 2758-2765, American Vacuum Society.	
ma		ANDERSON, H.M. et al., "Particulate Generation in Silane / Ammonia RF Discharges," <i>J. Applied Physics</i> , May 1, 1990, Vol. 67, No. 9, pp. 3999-4011, American Institute of Physics.	

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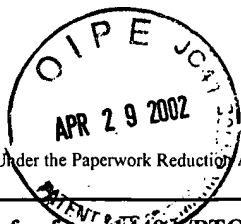
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ma		JELLUM, G.M. et al., "Particulates in Aluminum Sputtering Discharges," <i>J. Appl. Phys.</i> , May 15, 1990, Vol. 67 No. 10, pp. 6490-6496, American Institute of Physics.	
ma		SELWYN, G.S. et al., "In situ Plasma Contamination Measurements by HeNe Laser Light Scattering: A Case Study," <i>J. Vac. Sci. Technol.</i> , May / June 1990, A 8, (3) pp. 1726-1731, American Vacuum Society.	
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ma		AKARI, K. et al., "Reduction in Macroparticles During the Deposition of TiN Films Prepared by Arc Ion Plating," <i>Surface and Coatings Technology</i> , 1990, 43/44, pp. 312-323, Elsevier Sequoia, The Netherlands.	
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ma		SMADI, M.M. et al., "Particle Contamination on a Silicon Substrate in a SF <sub>6</sub> / Ar Plasma," <i>J. Vac. Sci. Technol.</i> , January/February 1992, B 10, (1) pp. 30-36, American Vacuum Society.	
ma		YOO, W.J. et al., "Kinetics of Particle Generation in Sputtering and Reactive Ion Etching Plasmas," <i>Appl. Phys. Letter</i> , March 2, 1992, Vol. 60, No. 9, pp. 1073-1075, American Institute of Physics.	
ma		LOGAN, J.S. et al., "Study of Particle Emission in Vacuum from Film Deposits," <i>J. Vac. Sci. Technol.</i> , July/August 1992, A 10, (4) pp. 1875-1878, American Vacuum Society.	
ma		GOREE J. et al., "Particulate Release from Surfaces Exposed to a Plasma," <i>J. Vac. Sci. Technol.</i> , November/December 1992, A 10, (6) pp. 3540-3544, American Vacuum Society.	

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ma		SCHOLL, R.A., "A New Method of Handling Arcs and Reducing Particulates in DC Plasma Processing," <i>Society of Vacuum Coaters 37th Annual Technical Conference Proceedings</i> , 1994, pp. 312-315, Advanced Energy Industries, Inc.	
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Examiner Signature	Melwyn Andrews	Date Considered	11-20-03
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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